



SEM3200



Scanning Electron Microscope SFM3200



Product Introduction

SEM3200 is a tungsten filament scanning electron microscope with high performance and wide application.

It has excellent imaging quality capabilities in both high and low vacuum modes. It also has a large depth of field with a user friendly environment to characterize samples. What's more, rich scalability helps the users to explore the world of microscopic imaging.

Resolution

High vacuum: 3 nm @ 30 kV (SE), 8 nm @ 3 kV (SE), 4 nm @ 30 kV (BSE) ¹Low vacuum: 3 nm @ 30 kV (SE)

Magnification [©]1~300,000x ;[®]1~1000,000x

Acceleration Voltage $0.2 \, \text{kV} \sim 30 \, \text{kV}$

①Low vacuum secondary electronic detector optional

⁽²⁾Magnification of film

③Magnification of screen

Product Advantages

(*optional)



Scalability SE\BSE\EDS\EBSD, etc



Mixing imaging (SE+BSE) The composition and surface information of the sample is observed in an image



Optical navigation quickly navigate the region of interest (ROI)



*Tetrode emission system Tetrode design provides excellent resolution under low landing energy



*Large image mapping Automatic image acquisition and stitching



*Low vacuum mode Provides sample surface details and morphology at low vacuum, and the software switches the vacuum state with one click



Product Features (*Optional)

Low voltage

For carbon material samples, at low voltage, the penetration depth is small, and the true morphology of the sample surface can be obtained with richer details.



For hair samples, at low voltage, the damage of electron beam irradiation is reduced and the charge effect is eliminated.



Low vacuum

The filter fiber tube material has poor electrical conductivity and obvious charge under high vacuum. Under low vacuum, the non-conductive sample can be directly observed without coating.





Wide field of view

Biological samples can easily obtain the overall morphology and head structure details of the ladybug by using wide-field observation, and display cross-scale analysis.



Navigation & Anti-collision

Optical navigation

The standard camera in the warehouse can take high-definition photos of the sample station and quickly locate the sample.



Gesture shortcut navigation

Box selection and magnification: under the low-power navigation, you can get a large field of view of the sample, which can quickly select the sample area you are interested in, improving work efficiency.



Anti-collision technology

Multi-dimensional anti-collision scheme:

- 1. Manually input the sample height to accurately control the distance between the sample and the lower end of the objective to prevent collision;
- 2. Based on image recognition and dynamic capture technology, real-time monitoring of the pictures in the warehouse in the process of movement;
- 3. Hardware anti-collision, can stop the motor at the moment of collision, reduce collision damage. (*SEM3200A requires this function)





Feature function

Intelligent assisted astigmatism

Directly reflect the astigmatism of the whole field of vision, through the mouse click clear, can quickly adjust the astigmatism to the best.



Autofocus

One-click focus for fast imaging.



Automatic astigmatism

One-click astigmatism, improve efficiency.





Automatic brightness contrast

One-click automatic brightness contrast, gray level appropriate image.



Image multiple information simultaneously

SEM3200 supports one-click switching between SE and BSE hybrid imaging, the morphology and composition information of samples can be observed simultaneously.



Fast image rotation

Drag a line and the image is instantly "angled".





Rich scalability

Scanning electron microscope is not only limited to the observation of surface morphology, but also can be used to analyze the micro-components of the sample surface.

In addition to conventional secondary electron detector (ETD), backscattered electron detector (BSED), and X-ray energy dispersive spectrometer (EDS), many interfaces are reserved, such as electron backscattered diffraction (EBSD), cathode ray (CL) detectors can be integrated on SEM3200.

Backscattered electron detector

Contrast between secondary electron imaging and backscattered electron imaging

In the backscattered electron imaging mode, the charge effect is weakened obviously, and more composition information can be obtained on the sample surface.

Coating sample:





Tungsten steel alloy sample:





Quadripartite backscattered electron detector -- multichannel imaging

The detector is exquisitely designed and highly sensitive. It adopts a 4-segment design, and can obtain shadow images and component distribution images in different directions without tilting the sample.



Four single-channel shadow images

X-ray energy dispersive spectrometer (EDS)

Composition image



Electron backscatter diffraction

Tungsten filament has a large electron microscope beam, which fully meets the testing requirements of high resolution EBSD. It can calibrate the crystal orientation and analyze the grain size of polycrystalline materials such as metals, ceramics and minerals.

The EBSD reverse polar diagram of Ni metal standard samples can identify grain size and orientation, grain boundaries and twins, and accurately judge the material structure.





Application

Semiconductors and electronic components





 SEM3200
 ETD SE
 HV 10kV
 MAG.S x15000
 HFW 27.09um
 WD 5.18mm
 Hgh V 1.2e-3Pa

 Chip-2
 Acceleration voltage:
 10 KV / magnification:
 ×15000

Acceleration voltage: 10 KV / magnification: ×30000

Batteries and new energy

Chip-1



 SEM3200
 ETD SE
 HV 5kV
 MAG.P x1000
 HFW 0.13mm
 WD 4.98mm
 Hgh.V 2.1e-3Pa

 Negative electrode -- carbon

Acceleration voltage: 5 KV/ Magnification: ×1000



 SEM3200
 ETD SE
 HV 10kV
 MAG.P. x1000
 HFW 0.13mm
 WD 4.51mm
 High.V 6.90-4Pa

 Negative electrode - carbon coated silicon

 Acceleration voltage: 10 KV/magnification: ×1000

10.00



 SEM3200
 ETD SE
 HV 15kV
 MAG x10000
 HFW 20.32um
 WD 10mm

 Positive electrode --Lithium cobaltate

 Acceleration voltage: 15 KV/ Magnification: ×10000



 SEM3200
 ETD SE
 HV 5kV
 MG.P x3000
 HFW 42.71um
 WD 6.03mm
 High.V 4.9e-4Pa

 Positive electrode --Lithium manganate

 Acceleration voltage: 5 KV/ Magnification: ×3000

08





MAG HFW WD x15000 27.09um 6mm 2um 5kV Solar cell-1

Acceleration voltage: 5 KV/ Magnification: ×10000

Polymer material



Polymer foam

Acceleration voltage: 15 KV/ Magnification: ×5000



Acceleration voltage: 10 KV/ Magnification: ×5000

Chemicals



HV 15kV 0.20mm 8mm x2000 Catalyst -MOF material Acceleration voltage: 15 KV/ Magnification: ×2000

Metal



SEM3200 BSED Comp HV 15kV x10000 40.64um 8mm 2A12 Aluminium alloy precipitated phase Acceleration voltage: 15 KV/ Magnification: ×10000



SEM3200 BSED HV MAG.S Comp 15kV x2000 0.20mm 6.91mm 3.4E-4Pa 1 Mg-ZnAlloy compound layer Acceleration voltage: 15 KV/ Magnification: ×2000





 SEM3200
 BSED Comp
 HV
 MAG.S x5000
 HFW
 WD
 High.V
 Frames

 Stainless steel - brass welds
 5.35mm
 8.4E-4Pa
 1
 10um

Acceleration voltage: 15 KV/ Magnification: ×5000



 SEM3200
 ETD SE
 HV 20kV
 MAG x30000
 HFW 13.55um
 WD 8mm
 HFW

 Titanium alloy matrix structure
 Acceleration voltage: 20 KV/ Magnification: ×30000
 HFW
 X0000
 HFW
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 HFW
 HFW</t



 SEM3200
 ETD SE
 HV 20kV
 MAG x5000
 HFW 81.28um
 WD 7mm
 HOUT

 Alloy fracture brittleness + toughness
 + toughness
 + coughness
 + c



Ductile fracture

Acceleration voltage: 20 KV/ Magnification: ×1000



Steel inclusion BSE Acceleration voltage: 15 KV/ Magnification: ×7000



SESteel inclusion SE Acceleration voltage: 15 KV/ Magnification: ×7000



Organism



Acceleration voltage: 10 KV/ Magnification: ×75000



 SEM3200
 ETD SE
 HV
 MAG.S
 HFW
 WD
 High.V

 Juitom-2
 10kV
 x35000
 11.61um
 6.48mm
 4.3e-4Pa
 1u

Acceleration voltage: 10 KV/ Magnification: ×35000

500nm



 SEM3200
 ETD
 HV
 MAG
 HEW
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 Staphylococcus galli-1
 15kV
 x20000
 20.32um
 7mm

 Acceleration voltage:
 15 KV/ Magnification:
 ×20000
 x20000
 x20000



 SEM3200
 ETD SE
 HV 15kV
 MAG x5000
 HFW 81.28um
 WD 7mm
 HT
 10um

 Staphylococcus galli-2
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Acceleration voltage: 15 KV/ Magnification: ×5000

Food



Rice Acceleration voltage: 10 KV/ Magnification: ×500



 SEM3200
 ETD SE
 HV 10kV
 MAG.S x5000
 HFW 81.28um
 WO 6.37mm
 High V 1.0E-3Pa
 Frames

 Glutinous rice starch granules-1
 Acceleration voltage: 10 KV/ Magnification: ×5000
 X5000
 X50000
 X5000
 X50000
 X5000
 X5000





10um

 SEM3200
 ETD SE
 HV 10kV
 MAG.S x5000
 HFW 81.28um
 WD 8.71mm
 High V 1.4E-3Pa
 Frames 1

 Glutinous rice starch granules-2
 Acceleration voltage: 10 KV/ Magnification: ×5000
 X5000
 X5000



 SEM3200
 ETD SE
 HV 1kV
 MAG.S x500
 HFW 0.81mm
 WD 6.91mm
 High.V 5.9E-4Pa
 Frames

 Damp salt particles
 Acceleration voltage: 1 KV/ Magnification: ×500
 100um
 100um

Basic research



SEM3200 SE HV MAG HFW W0 SE 15kV x2000 0.20mm 6mm H Powder - Magnesium sulfate Acceleration voltage: 15 KV/ Magnification: ×2000



 SEM3200
 ETD SE
 HV 25kV
 MAG.S x48000
 HFW 8.47um
 WD 5.93mm
 High.V 7.3E-4Pa
 Lines

 Powder - barium titanate
 Acceleration voltage: 25 KV/ Magnification: ×48000
 X48000
 <td



Powder alpha-alumina Acceleration voltage: 15 KV/ Magnification: ×10000



 SEM3200
 BSED Comp
 HV 10kV
 MAG.S x10000
 HFW 40.64um
 WD 7.23mm
 Hgh.V 6.9e-4Pa

 Filter function material
 Acceleration voltage: 10 KV/ Magnification: ×10000
 X10000
 X10000

5um



Basic research



 SEM3200
 ETD SE
 HV 20kV
 MAG.S x50000
 HFW 8.13um
 WD 7.91mm
 High.V 4.4E-4Pa

 Nanomaterial - silica microspheres

Acceleration voltage: 20 KV/ Magnification: ×50000

Environment

1um



 SEM3200
 BSED Comp
 HV
 MAG 15kV
 HFW
 WD

 Rock
 15kV
 x1000
 0.41mm
 13mm
 50um

Acceleration voltage: 15 KV/ Magnification: ×1000

Ceramic



SEM3200 BSED HV MAG.S HFW WD High V Frames Comp 15kV x1000 0.41mm 11.91mm 1.4E-3Pa 1 50um SiC ceramic BSE

Acceleration voltage: 15 KV/ Magnification: ×1000



SEM3200 SE 15kV x1000 0.41mm 11.91mm 1.4E-3Pa 1 SiC ceramic SE

Acceleration voltage: 15 KV/ Magnification: ×1000



 SEM3200
 ETD SE
 HV 15kV
 MAG x5000
 HFW 81.28um
 WO 6mm

 Ceramic composite
 Acceleration voltage: 15 KV/ Magnification: ×5000
 X5000
 X5000



- 5um

SEM3200 ETD HV MAG HFW WD Ceramic structural material Acceleration voltage: 5 KV/ Magnification: ×10000



Products Specifications (*Optional)

Model			SEM3200A	SEM3200
Electron optical system	Electron gun		Pre-aligned medium-sized fork-type tungsten filament	
	Resolution	High vacuum	3 nm @ 30 kV (SE) 4 nm @ 30 kV (BSE) 8 nm @ 3 kV (SE)	
		*Low vacuum	3 nm @ 30 kV (SE)	
	Magnification		1~300,000x (film)	
			1~1000,000x (screen)	
	Accelerating voltage		0.2 kV~30 kV	
Imaging system	Detector		Secondary electron detector (ETD)	
			*EBSD、*Low vacuum SED、*EDS	
	Image format		TIFF、JPG、BMP、PNG	
Vacuum system	Vacuum mode	High vacuum	Better than 5×10 ⁻⁴ Pa	
		*Low vacuum	5~1000 Pa	
	Control mode		Full automatic	
	Turbo molecular pump		≥ 240 L/S	
	Mechanical pump		200 L/min (50 Hz)	
Sample room	Camera		Optical navigation	
			Monitoring	
	Sample stage		Three axis automatic	Five axis automatic
	Distance		X: 120 mm	X: 120 mm
			Y: 115 mm	Y: 115 mm
			Z: 50 mm	Z: 50 mm
			/	R: 360°
			/	T: -10°∼ +90°
Software	Language		Chinese/English	
	OS		Windows	
	Navigation		Optical navigation, gesture quick navigation	
	Automatic function		Auto brightness contrast, auto focus, auto astigmatism	
	Featured function		Intelligent assisted astigmatism, maximum image Mosaic (optional software)	
Installation Requirements	Size		$L \ge 3000 \text{ mm}, \text{ W} \ge 4000 \text{ mm}, \text{H} \ge 2300 \text{ mm}$	
	Temperature		20 °C∼25 °C	
	Humidity		≤ 50 %	
	Electrical power		AC 220 V(±10 %), 50 Hz, 2 kVA	



Hefei, China

Wuxi, China

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